

isothiazolin-3-one, wherein said fungicide is present in an amount of from 5 to 10% by weight, and

c) a stabilizer selected from the group consisting of 2-mercaptopyridine N-oxide, metal or ammonium salts of 2-mercaptopyridine N-oxide, metal salt complexes of 2-mercaptopyridine N-oxide, 2,2'-dithiobis(pyridine N-oxide), 2-mercaptobenzothiazole, 2-thiocyanomethyl-thiobenzothiazole, NaBrO₃ and mixtures thereof, wherein said stabilizer is present in an amount of 5 to 10% by weight.

--30. (new) The composition according to claim 29, wherein said bactericidal is 2,2',2''-(hexahydro-1,3,5-triazine-1,3,5-triyl)tri-ethanol.

--31. (new) The composition according to claim 29, further comprising solvents and/or solubility promoters.

--32. (new) The composition according to claim 31, wherein said solvent is selected from the group consisting of alcohol, ether, glycol, glycol monoether, glycol diether, polyol, polyol monoether, and mixtures thereof.


--33. (new) The composition according to claim 31, wherein said solvent is selected from the group consisting of phenoxyethanol, phenoxypropanol, 1,2-propylene glycol, 1-methoxy-2-propanol, diethylene glycol butyl ether and dipropylene glycol.

--34. (new) The composition according to claim 31, wherein solvent is present in an amount of less than 25% weight of said composition.

--35. (new) The composition according to claim 29, further comprising a complexing agent.

--36. (new) The composition according to claim 35, wherein the complexing agent is selected from the group consisting of phosphates, polyphosphates, ethylenediaminetetraacetic acid, nitriloacetic acid, N,N-bis(2-hydroxyethyl)glycine, diethylenetriaminepentaacetic acid, hydroxyethanediphosphonic acid, gluconic acid, hydroxyethylethylenediaminetriacetic acid, polyoxycarboxylic acid, tris(aminomethyl)phosphonic acid, diethylenetriaminepentamethylenephosphonic acid, ethylenediaminetetramethylenephosphonic acid, ethylenediaminedisuccinic acid, polyaspartic acid, methylglycinediacetic acid and salts of said acids.

--37. (new) The composition according to claim 29, further comprising corrosive-protective agents.

 --38. (new) The method according to claim 37, wherein the corrosive protective agent is selected from the group consisting of phosphonobutanetricarboxylic acid, salts of

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phosphonobutanetricarboxylic acids, triazole, benzotriazole, methylbenzotriazole, 2,2'-[[(methyl-1H-benzotriazol-1-yl)methyl]imino]bisethanol, N,N-bis(2-ethylhexyl)-4-methyl-1H-benzotriazole-1-methylamine, and carboxy-4-hexylcyclohe-2-en-1-octanoic acid.

--39. (new) The composition according to claim 29, further comprising O-formals.

--40. (new) The composition according to claim 29, wherein said composition is in the form of liquid, liquid-viscous or paste.

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--41. (new) The method according to claim 29, wherein said composition is in the form of a concentrate.

--42. (new) The method according to claim 29, wherein said composition is in the form of a ready-to-use solution.

--43. (new) A method for achieving a microbicidal effect in industrial products comprising applying to an article or surface an effective amount of a composition according to claim 29.

--44. (new) The method according to claim 43, wherein said composition is used in a concentration greater than 0.01% by weight.

--45. (new) The method according to claim 43, further comprising adding said bactericidal, fungicidal and stabilizer to said composition separate from each other.

--46. (new) The method according to claim 43, further comprising heating said bactericidal component, fungicidal component and stabilizer component, followed by adding said components to said mixture.

--47. (new) A process for the preparation of a composition according to claim 1, comprising heating said bactericidal component, said fungicidal component and said stabilizer component, and adding said components to one another.

--48. (new) An industrial product comprising a composition according to claim 1.--

R E M A R K S

This application has been amended in a manner that places it in condition for allowance at the time of the next Official Action.